





U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					98-0001-1		09/518,970 10649186	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant(s)			
(Use several sheets if necessary)					Tom A. Watson et al.			
					Filing Date		Group	
					March 6, 2001 8-26-03		1762-2828	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AL	AA	4,890,294	12/26/89	Nishimae et al.	372	57	/	
AL	AB	5,009,963	04/23/91	Ohmi et al.	428	472.2		
AL	AC	5,897,847	04/27/99	Jursich et al.	423	219		
AL	AD	6,024,885	02/15/00	Pendharkar et al.	216	22		
	AE							
	AF							
	AG							
	AH							
	AI							
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	AK							
	AL							
	AM							
	AN							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
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	AP							
	AQ							
	AR							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
/	AS							
	AT							
	AU							
Examiner		Date Considered						
AL		3-3-05						

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U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-7697 US		10649186	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT					Applicant(s)			
(Use several sheets if necessary)					Tom A. Watson et al.			
					Filing Date		Group	
					8-26-2003		2828 Unknown	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AK	AA	5,047,115	09/10/1991	Charlet et al.	156	643		
AK	AB	5,444,259	08/22/1995	Ohmi	250	452.21		
AK	AC	5,360,768	11/01/1994	Ohmi et al.	437	238		
	AD							
	AE							
	AF							
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	AI							
	AJ							
	AK							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
AK	AL	EP 0794 598 A1	10/09/1997	Europe				
	AM							
	AN							
	AO							
	AP							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
AK	AQ	Ultra Clean Manufacturing Technology Co., Ltd., "CRP & FP - Gas Supply System for the Next Generation of ULSI," (Undated) 16 pages						
AK	AR	N. Miki et al., "Vapor-Liquid Equilibrium of the Binary System HF-H ₂ O Extending to Extremely Anhydrous Hydrogen Fluoride," (March 1990) J. Electrochem. Soc., Vol. 137, No. 3, ©The Electrochemical Society, Inc., pages 787 - 790						
AK	AS	N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 - 1869						
Examiner		H. Rodriguez		Date Considered		3-3-05		
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	AA							
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		Document	Date	Country	Class	Subclass	Yes	No
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
AR	AQ	N. Maeno, et al., "Fluorine Passivation of Metal Alloy Surface With Volatile Reaction Enhanced mechanism," (July 1992) J. Electrochem. Soc., Vol. 139, No. 7, pages 1865 - 1869						
AR	AR	Phil Danielson, "Gas Loads From Elastomer Seals," (January 1999) Vacuum & Thinfilm, pages 14 - 15						
AR	AS	STELLA CHEMIFA Corporation, "Fluorine Passivation Technology," (1998) 11 pages						
Examiner		Armando Rodriguez		Date Considered		3-3-05		
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	AL							
	AM							
	AN							
	AO							
	AP							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
AR	AQ	N. Maki et al., "Fluorine Passivation of Metal Surface for Self-Cleaning Semiconductor Equipment," (February 1990) IEEE Transactions on Semiconductor Manufacturing, Vol. 3, No. 1, pages 1 - 11						
AR	AR	M. Maeno et al., "Optimization of Fluorine Passivation of Stainless Steel Surfaces," (May 1992) IEEE Transactions on Semiconductor Manufacturing, Vol. 5, No. 2 pages 107 - 113						
AS	AS	Hashimoto Chemical Corporation, "Fluorine Passivation Technology," (1997) pages 1 - 11						
Examiner		Armando Rodriguez		Date Considered		3-3-05		
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U.S. Department of Commerce, Patent and Trademark Office				Atty Docket No.		Serial No.		
				M-7697 US		10644166		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant(s)				
(Use several sheets if necessary)				Tom A. Watson et al.				
				Filing Date		Group		
				8-26-03		2826 Unknown		
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA							
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Foreign Patent Documents								
							Translation	
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	AL							
	AM							
	AN							
	AO							
	AP							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
	AQ	M. Maeno et al., "Fluorine-Passivated Electroless Ni-P Films," (October 1994) J. Electrochem. Soc., Vol. 141, No. 10, ©The Electrochemical Society, Inc., pages 2649 - 2654						
	AR	G.M. Jurisch et al., "Gas Contaminant Effects in Discharge-Excited KrF Lasers," (April 20, 1992) Applied Optics, Vol. 31, No. 12, pages 1974 - 1981						
	AS	W. Holber et al., "Reducing PFC Emissions From CVD Reactors," (March 1999) Vacuum & Thinfil, pages 26 - 29						
Examiner				Date Considered		3-3-05		
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)	Applicant(s) Tom A. Watson et al.	
	Filing Date 8-26-03	Group 2828
		Unknown

U.S. Patent Documents

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	AA						
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Foreign Patent Documents

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	AL							
	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AL	AQ	Future Fab International, "XPS Analysis on Fluorine Removal by Plasma Cleaning," (Undated) pages 289 - 293
AL	AR	P.M. Clarke et al., "Gas-Phase Interactions Between WF ₆ and Metal Surfaces," (1994) Conference Proceedings ULSI-IX - Materials Research Society, pages 411 - 417; 59 68
AL	AS	Y. Shirai et al., "Fluorine Passivation of Metal Surface," (1996) CleanRooms "'96 West Session 602, pages 68 - 71

Examiner *Armando Rodriguez* Date Considered 3-3-05

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U.S. Department of Commerce, Patent and Trademark Office				Atty Docket No.		Serial No.	
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Applicant(s)			
(Use several sheets if necessary)				Tom A. Watson et al.			
				Filing Date		Group	
				8-26-03		2828 Unknown	
U.S. Patent Documents							
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							Translation
		Document	Date	Country	Class	Subclass	Yes No
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	AM						
	AN						
	AO						
	AP						
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)							
AL	AQ	Phil Danileson, "Rate-of-rise Measurements," (November/December 1998) Vacuum & Thinfil, pages 12 - 13					
AL	AR	Vacuum & Thinfil, "The Evolution of RF," (November/December 1998) pages 30 - 33					
AL	AS	Y. Minamitani et al., "Characteristics of A Corona Reactor As A Gas Purifier For Excimer Lasers," (Undated) pages 1 - 18					
Examiner <i>AL</i>		Date Considered <i>3-3-05</i>					
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	AA								
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	AN								
	AO								
	AP								
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)									
AL	AQ	H.E. Litvak, "End Point Control Via Optical Emission Spectroscopy," (1996) J. Vac. Sci. Technol. B14(1), pages 516 - 520							
AL	AR	D.W. Greve et al., "Process Control Based On Quadrupole Mass Spectrometry," (1996) J. Vac. Sci. Technol. B14(1), pages 489 - 493							
AL	AS	Los Alamos National Laboratory, "Excimer Laser Chemical Problems," (1985) U.S. Dept. of Commerce, 81 pages							
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	AA						
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	AL							
	AM							
	AN							
	AO							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AL	AP	Kazuhide Ino et al., "Plasma Enhanced <i>In Situ</i> Chamber Cleaning Evaluated by Extracted-Plasma-Parameter Analysis," (1996) IEEE Transaction on Semiconductor Manufacturing, Vol. 9, No. 2, pages 230 - 240
AL	AQ	Kenji Komine et al., "Residuals Caused by The CF ₄ Gas Plasma Etching Process," (May 1996) Jpn. J. Appl. Phys. Vol. 35, pages 3010 - 3014
AL	AR	A.L. Cabrera et al., "Surface Analysis Of Copper, Brass, and Steel Foils Exposed to Fluorine Containing Atmospheres," (1990) J. Vac. Sci. Technol. A8, pages 3988 - 3996
AL	AS	I. Kazuhide et al., " <i>In Situ</i> Chamber Cleaning Using Halogenated-Gas Plasmas Evaluated by Plasma-Parameter Extraction," (January 1994) Jpn. J. Appl. Phys. Vol. 33, pages 505 - 509

Examiner A. P. [Signature] Date Considered 3-3-05

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